				Atty. Docket No.	Serial N	o.: 09/901,6	557	
Form PTO-1449 (Rev. 2-32)		U.S. Department of Commerce Patent & Trademark Office		Q65210	Confirm	Confirmation No.: 7845		
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				Applicant: Tsuyoshi NAKAMURA, et al.				
				Filing Date: July 11, 2001	Group: 1756			
U.S. PATENT DOCUMENTS								
Examiner Initial		Document Number	Date	Name	Class	Sub- Class	Filing Date (if appropriate)	
445		5,234,793	08/10/1993	Sebald et al.				
ACC PE		5,234,794	08/10/1993	Sebald et al.				
19a	18	5,250,375	10/05/1993	Sebald et al.				
4 cet a south		6,110,637	08/29/2000	Sezi et al.				
AUG 3 0 2000	<u> </u>							
B	,¢/					DEC		
The most	<u> </u>				•			
PARADEM!						- SEP	1 0 2001	
						V		
						T. C	1700	
	ļ							
				<u></u>	-			
	·							
FOREIGN PATENT DOCUMENTS								
		Document	Date	Country	Class	Sub- class	Translation Yes/No	
40		11-212265	08/06/1999	Japan			Abstract	
J								
	ļ —							
	Lines, Pers		TEG (I I II	A d Win D D)	E4-)		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
ycr	Sebald et al., Chemical Amplification of Resist Lines (CARL), Microelectronic Engineering, pp. 531-534							
 		4						
EVAMINED.	21-	CAL		DATE CONSIDERE	ED: 4/	11-0	2	
EXAMINER: 7	quil	m - Min		I DATE CONSIDER	D. 7-	11-0	2	
EXAMINER. Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication.								